

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Woo Sup SHIN, et al.

Serial No.: 09/039,438

Filed: March 16, 1998

For: Etching Apparatus

Group Art Unit: 1763

Examiner: R. Zervigon

AMENDMENT

Commissioner of Patents
Washington, D.C. 20231

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Sir:

In response to the Office Action mailed March 25, 2002, the following amendments and remarks are respectfully submitted.

IN THE CLAIMS:

Please amend the claims as follows (A marked-up version of the amended claims is attached):

1. (Amended) An etching apparatus for etching a glass substrate comprising:
- a first tank including a first etchant;
 - an etch bath for immersing said glass substrate in said first etchant, said etch bath having a bubble plate, the etch bath being connected to the first tank and receiving the first etchant, the etch bath containing a residual etchant including a diluted etchant and residue material after the glass substrate is etched with the first etchant to uniformly reduce a thickness of the glass substrate;
 - a second tank for receiving the residual etchant from the etch bath and separating the diluted etchant from the residue material;